

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor:	Patrick Schiavone, et al.	§	Atty.Dkt.No.:	5957-07300
Serial Number:	09/462,716	§	Examiner:	Alexander G. Ghyka
Filing Date:	August 6, 2001	§	Group/Art Unit:	2812
Title:	METHOD FOR MINIMIZING THE CORNER EFFECT BY DENSIFYING THE INSULATING LAYER	§ § § § § § §	Conf. No.:	5431

LETTER TO EXAMINER

Mail Stop Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

I would like to bring to your attention the following reference, which was cited in the International Search Report and provided to the Patent Office, but which does not appear to have been officially considered:

Gaillard, F, et al., Silicon Dioxide Chemical Vapor Deposition Using Silane and Hydrogen Peroxide, 7/1/96, pp. 2767-2769.

Respectfully submitted,

Date: July 5, 2007

By: /Dean M. Munyon/
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